

IN THE CLAIMS:

The text of all pending claims, (including withdrawn claims) is set forth below. Cancelled and not entered claims are indicated with claim number and status only. The claims as listed below show added text with underlining and deleted text with ~~striketrough~~. The status of each claim is indicated with one of (original), (currently amended), (cancelled), (withdrawn), (new), (previously presented), or (not entered). Please AMEND claims 7, 14 and 17 and CANCEL claims 1-6, 8 and 13 without prejudice or disclaimer in accordance with the following:

1. (cancelled)
2. (cancelled)
3. (cancelled)
4. (cancelled)
5. (cancelled)
6. (cancelled)
7. (currently amended) A plasma display panel comprising:
a dielectric layer in which a filler for enhancing reflectance is dispersed; and
barrier ribs for partitioning a discharge space, wherein sidewalls of the barrier ribs
are covered with the dielectric layer,
wherein the filler comprises pieces individually having outward appearance of flakes whose front and back faces are oriented in a direction along a surface of the dielectric layer, and the dielectric layer is formed using a hollow form provided with recesses in a pattern corresponding to the form of the barrier ribs and has a dielectric constant ≤ 10 ,
wherein the filler is mica coated with titanium dioxide.
8. (cancelled)
9. (original) A plasma display panel according to claim 8, wherein the dielectric

layer contains a low-melting-point glass as a base material.

10. (original) A plasma display panel according to claim 9, wherein the content of the filler in the dielectric layer is a value within the range of 10 to 80 wt%.

11. (original) A plasma display panel according to claim 8, wherein the dielectric layer contains silicon oxide as a base material.

12. (original) A plasma display panel according to claim 11, wherein the content of the filler in the dielectric layer is a value within the range of 10 to 80 wt%.

13. (cancelled)

14. (currently amended) A plasma display panel according to claim ~~13~~ 7, wherein the barrier ribs are black.

15. (previously presented) A plasma display panel according to claim 14, wherein the black barrier ribs have a transmission per unit length of 10 %/ 10 μm or less to visible light.

16. (previously presented) A plasma display panel according to claim 14, wherein the dielectric layer has a reflectance per unit length of 50 % / 10 μm or more.

17. (currently amended) A substrate structure to be used for fabrication of a plasma display panel as set forth in claim ~~13~~ 7, which is provided with the barrier ribs and the dielectric layer.

18. (original) A substrate structure according to claim 17, wherein the barrier ribs are black.

19. (previously presented) A plasma display panel according to claim 7, wherein a light-shielding layer is provided on a front side with respect to a discharge space and the dielectric layer is provided on a rear side with respect to the light-shielding layer.

20. (original) A substrate structure to be used for fabrication of a plasma display panel as set forth in claim 19, wherein the light-shielding layer and the dielectric layer are provided on a substrate.

21. (withdrawn) A process for manufacturing a substrate structure wherein, in manufacture of the substrate structure as set forth in claim 17, the dielectric layer is formed by applying onto a substrate a low-melting-point glass paste in which a flake-form filler for enhancing reflectance is mixed, followed by burning.

22. (withdrawn) A process for manufacturing a substrate structure according to claim 21, wherein the dielectric layer is formed by applying onto a supporting face a low-melting-point glass paste in which flake-form mica coated with titanium dioxide and particulate titanium dioxide are mixed, followed by burning.

23. (withdrawn) A process for manufacturing a substrate structure according to claim 22, wherein the mixture ratio of the particulate titanium oxide to the flake-form mica is a value within the range of 5 to 30 wt%.

24. (withdrawn) A process for manufacturing a substrate structure according to claim 23, wherein the particulate titanium dioxide has a particle diameter of 5 μm or less.

25. (withdrawn) A process for manufacturing a substrate structure wherein, in manufacture of the substrate structure as set forth in claim 17, the dielectric layer is formed by applying onto a substrate a colloidal silica in which a flake-form filler for enhancing reflectance is mixed, followed by burning.

26. (withdrawn) A process for manufacturing a substrate structure wherein, in manufacture of the substrate structure as set forth in claim 17, the dielectric layer is formed by attaching to a supporting face a dielectric sheet in which a flake-form filler for enhancing reflectance is dispersed in a state such that the filler is uniformly oriented.

27. (withdrawn) A process for manufacturing a substrate structure wherein, in manufacture of the substrate structure as set forth in claim 17, the dielectric layer is formed by attaching and setting to a hollow form a dielectric sheet in

which a flake-form filler for enhancing reflectance is dispersed in a state such that the filler is uniformly oriented, and then transferring the dielectric sheet to a substrate.